# 2D-Nanometrology using Model 300-2D calibration specimen

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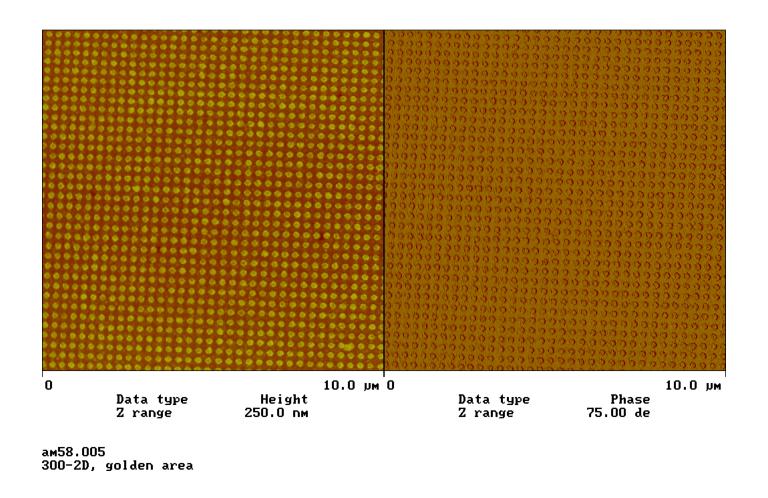
# Example of 2D Nanometrology

- Round-robin project of several national labs measures:
  - Pitch along X axis
  - Pitch along Y axis
  - Angle between X and Y axes
- This report shows imaging using a commercial open-loop AFM and data analysis using ASM's software.

### Materials and Methods

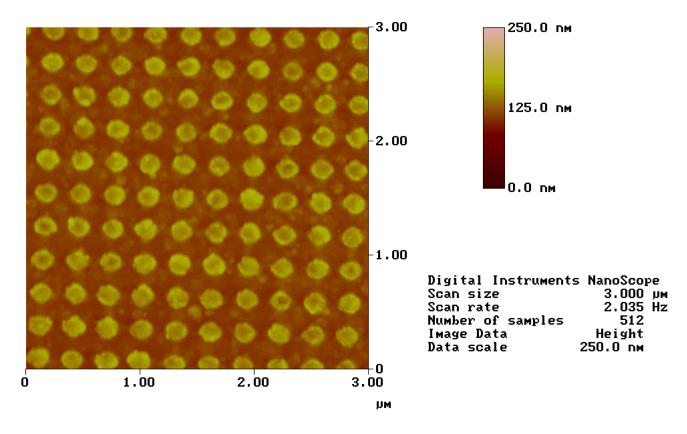
- NanoScope Dimension 3100 AFM
- Si tapping mode probe
- Model 300-2D specimen (s/n 2336E0210)
- Most images were captured with 512 pixels/line x 256 lines.

# AFM images of typical surface region (golden appearance in bright field reflected light)



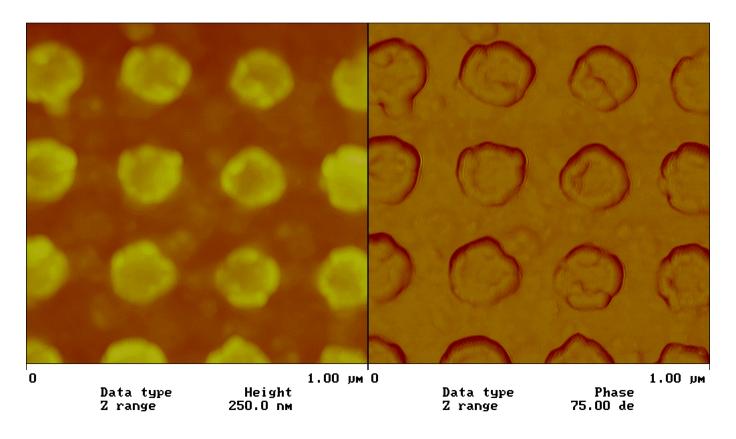
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### Golden region



300-2D, golden area am58.004

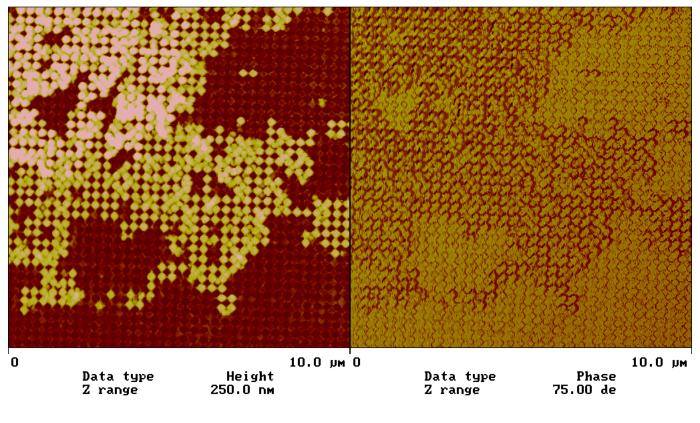
### Golden region



ам58.003 300-2D, golden area

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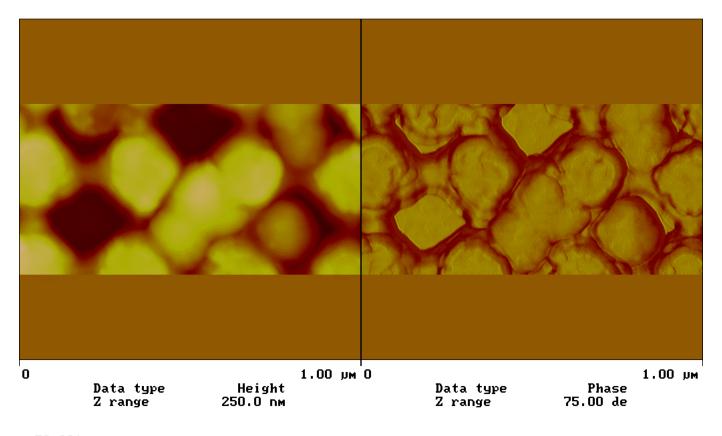
### At a small spot that appears dark in bright field reflected light



ам58.f02 300-2D, dark spot

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### Dark spot



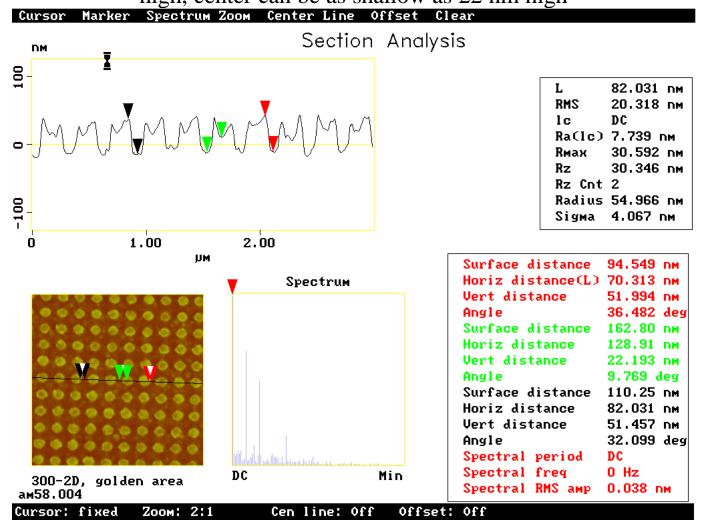
ам58.001 300-2D, dark spot

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### **Section Analysis**

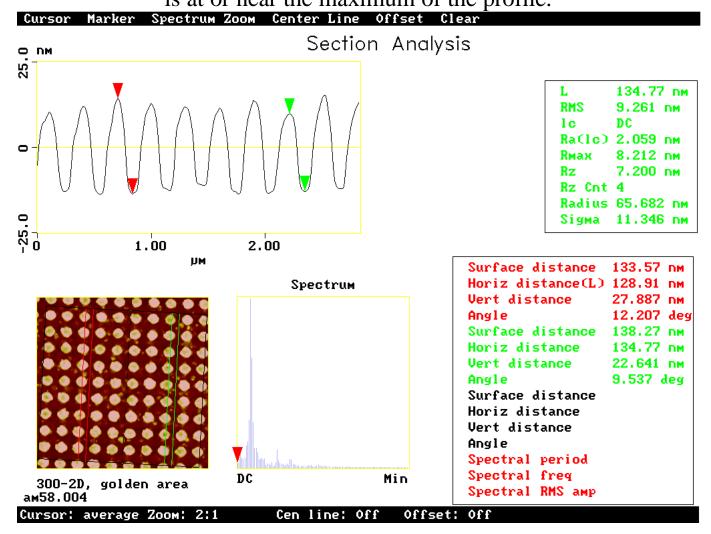
• Use NanoScope to manually draw and display single and average section profiles.

single line section profile shows some height variation – edge of crater is 52 nm high, center can be as shallow as 22 nm high



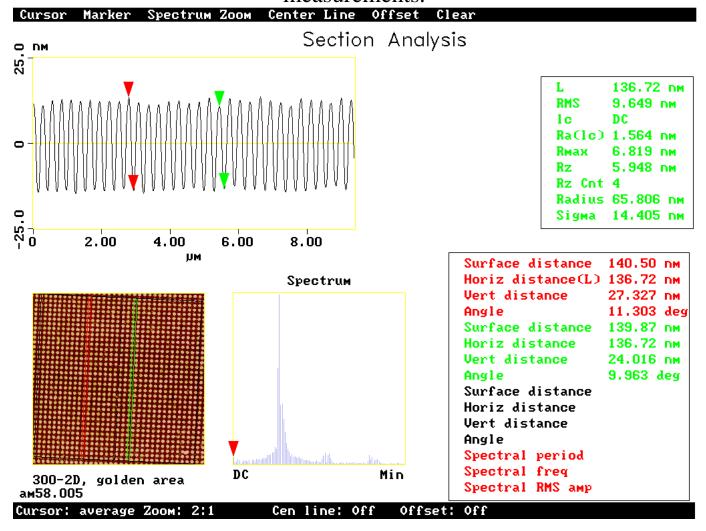
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an average cross-section has much less height variation and the center of a column is at or near the maximum of the profile.



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An average cross-section in the 10 um image would be good for pitch measurements.

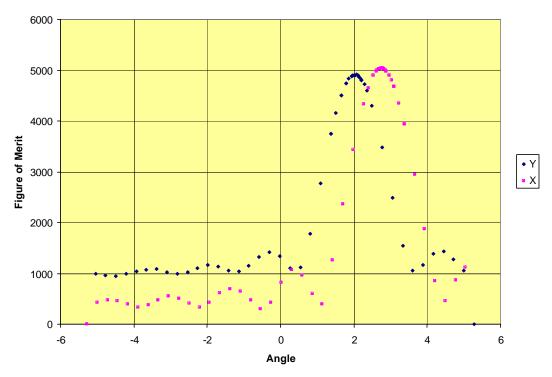


Make average cross-sections by an automated procedure free of operator error.

- Use ASM's Autoskew rev7.exe to automatically compute best averaging direction of X and Y section profiles
- "X" means the section direction is approximately parallel to the X axis.
- The analysis shows non-orthogonality of 0.7 degrees not a surprise. We did nothing to measure or correct for AFM drift.

# Section Orientation and non-orthogonality of image (we did not measure or correct for drift)

#### **Section Orientation**



2.749	degrees	X section
2.074	degrees	Y section
	degrees non-	
0.674	orthogonality	

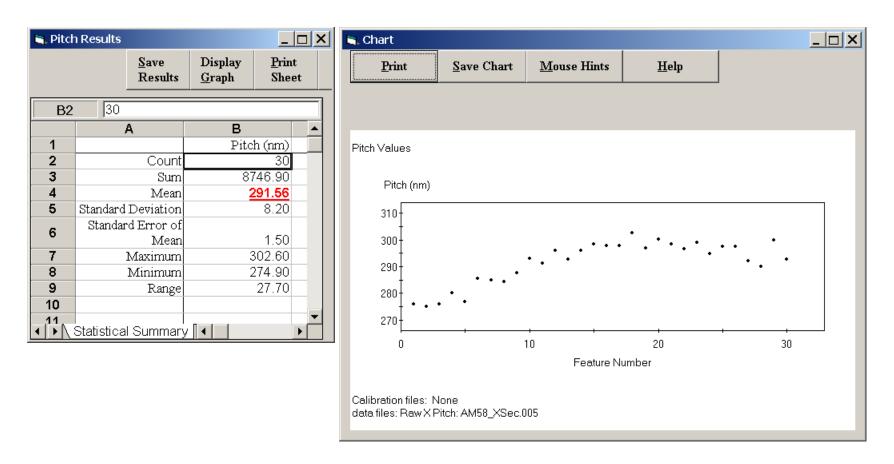
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# Pitch Analysis

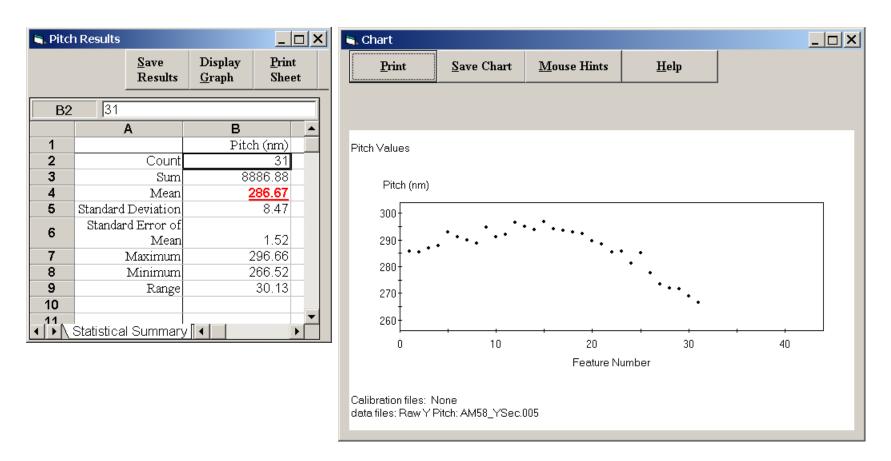
- Use ASM's DiscTrack Plus software
- We first present raw pitch measurements for average cross-sections from the 10 um image. The standard deviation is large because of systematic effects: residual nonlinearity in the AFM scanner.
- We then present self-calibrated pitch results. These amount to an offline correction of the AFM's nonlinearity.
- The standard deviation indicates residual error that may be related to AFM noise, pattern error, pattern feature roughness, etc.

### Raw Pitch Results

# DiscTrack Plus raw Pitch analysis of X average cross-section profile of 10 um image

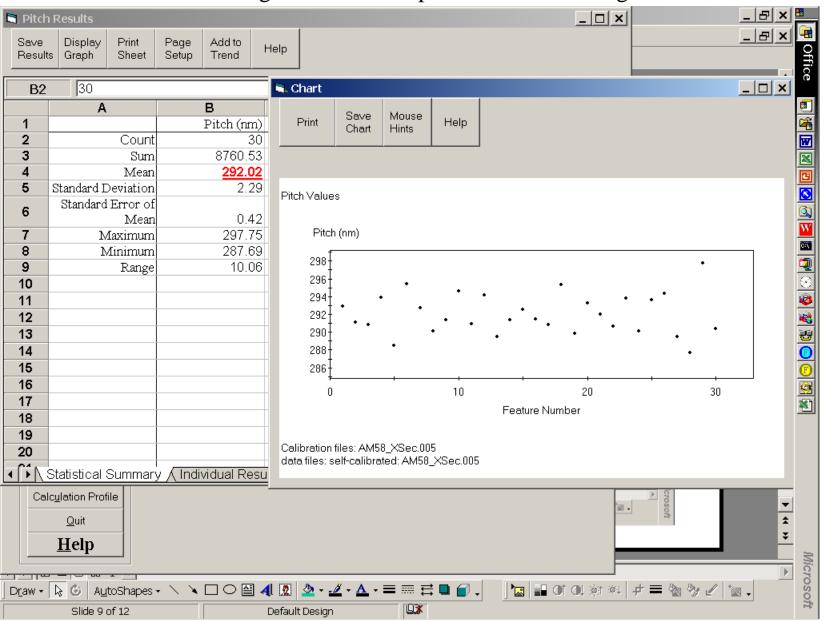


# DiscTrack Plus raw Pitch analysis of Y average cross-section profile of 10 um image



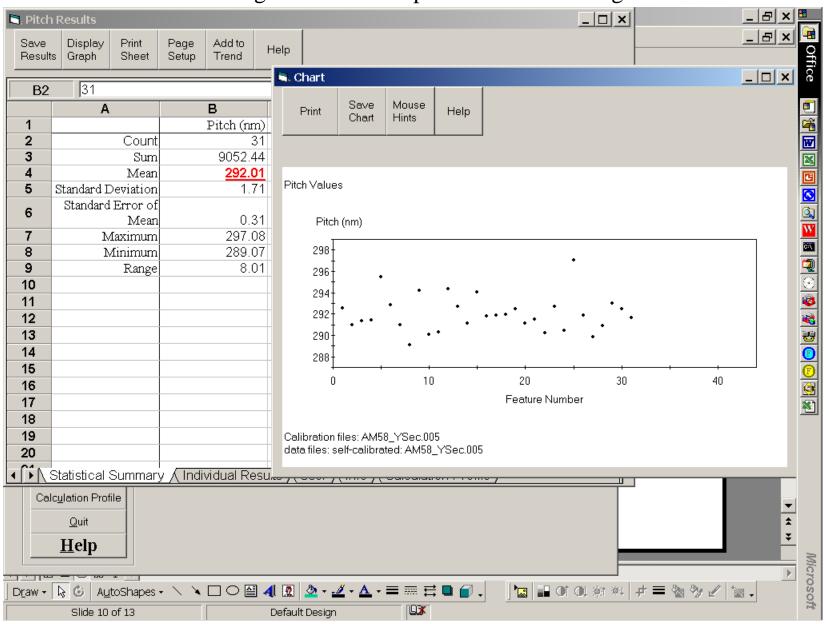
### Self-Calibrated Pitch Results

### DiscTrack Plus Self-calibrated Pitch analysis of X average cross-section profile of 10 um image



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# DiscTrack Plus Self-calibrated Pitch analysis of Y average cross-section profile of 10 um image



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### Further Reading

- "Automated, high precision measurement of critical dimensions using the Atomic Force Microscope", Donald A. Chernoff and David L. Burkhead, J. Vac. Sci. Technol. A 17, 1457 (1999).
- "High precision calibration and feature measurement system for a scanning probe microscope", Donald A. Chernoff and Jason D. Lohr, U.S. Patent # 5,644,512, issued July 1, 1997.
- "High precision calibration and feature measurement system for a scanning probe microscope", Donald A. Chernoff and Jason D. Lohr, U.S. Patent # 5,825,670, issued October 20, 1998.